



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

28248

In re Application of:
Huang, et al

Serial No.: 09/902,518

Confirmation No.: 7428

Filed: July 10, 2001

For: Method and Apparatus for Treating
Low K Dielectric Layers to Reduce
Diffusion

Commissioner for Patents
Washington, D.C. 20231

§
§
§ Group Art Unit: 2824
§
§ Examiner: Michael Lebentritt

8/A Ande
1-7-03
A. Wall

CERTIFICATE OF MAILING
37 CFR 1.8

I hereby certify that this correspondence is being deposited on December 17, 2002 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231.

12/17/2

Kent 2. L. b.

Dear Sir:

RESPONSE TO OFFICE ACTION DATED SEPTEMBER 27, 2002

In response to the Office Action dated September 27, 2002, having a shortened statutory period for response set to expire on December 27, 2002, Applicant requests entry and consideration of the following amendments and remarks. The Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/4180/DSM/BCVD/KMT, in the amount of \$156.00 for 1 additional independent claim and 4 total new claims, and any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

IN THE CLAIMS:

Please cancel claims 3 and 26 without prejudice, and amend the claims as follows:

1. (Amended) A method for processing a substrate, comprising: